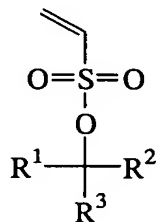


ABSTRACT

A sulfonate compound having formula (1) is novel
5 wherein R^1 to R^3 are H, F or C_{1-20} alkyl or fluoroalkyl, at
least one of R^1 to R^3 contains F. A polymer comprising units
derived from the sulfonate compound is used as a base resin
to formulate a resist composition which is sensitive to
high-energy radiation, maintains high transparency at a
10 wavelength of up to 200 nm, and has improved alkali
dissolution contrast and plasma etching resistance.



(1)